

08/221,375".

✓ Page 5, ✓ line 8, delete "The Detailed Description from U.S. patent application
Ser. No. 08/221,375".

✓ Page 7, line 22, change "274, 274" to --278, 278'--.

✓ Page 10, line 18, after "1 mm." insert ✓-Thus, the XY stage 230 is coupled to followers

B¹ 272, 282 of the reaction frame 261 exclusively by the Lorentz force between the magnet drive tracks (278, 278', 288, 288') and their corresponding coils (242X, 242X', 244Y, 244Y')--

✓ Page 13, line 20, delete "The Detailed Description from U.S. patent application
Ser. No. 08/416,558".

✓ IN THE CLAIMS:

✓ Please amend claim 5 as follows:

B² 5. (Amended) A lithographic device as claimed in claim 4, wherein the mask holder is displaceable perpendicularly to the Z-direction by means of [said] a mask holder positioning device that is similar to the positioning device of the substrate holder, and wherein [the] a first frame of the mask holder positioning device [of the mask holder] belongs to the machine frame of the lithographic device, while [the] a second frame of the mask holder positioning device [of the mask holder] belongs to the force frame of the lithographic device.

REMARKS

Claims 1-6 are pending. By this Amendment, the specification is amended as requested in item 1 of the Office Action. Additionally, claim 5 is amended for clarity, a typographical informality is corrected on page 7, and page 10 is amended to provide antecedent basis in the specification for the features recited in claim 2, as requested in the Office Action. No new matter is added.